

**AMENDMENTS TO THE CLAIMS**

**This listing of claims will replace all prior versions and listings of claims in the application:**

**LISTING OF CLAIMS:**

**1-3. (canceled).**

**4. (currently amended):** A method for the production of a support for a lithographic printing plate precursor that comprises:

providing on a grained aluminum support having an anodic oxide film formed thereon a layer of inorganic compound particles having a major axis larger than a pore diameter of the anodic oxide film;

treating the layer of inorganic compound particles with a treating solution capable of dissolving the inorganic compound particles, the treating solution comprising a compound containing fluorine, thereby fusing together the inorganic compound particles to form a layer of the inorganic compound; and

conducting a hydrophilic surface treatment with an aqueous solution containing a silicate.

**5. (previously presented):** The method for production of a support for a lithographic printing plate precursor as claimed in claim 4, wherein the inorganic compound particles comprises at least one selected from the group consisting of  $\text{Al}_2\text{O}_3$ ,  $\text{TiO}_2$ ,  $\text{SiO}_2$  and  $\text{ZrO}_2$ .

**6. (previously presented):** The method for production of a support for a lithographic printing plate precursor as claimed in claim 4, wherein the layer of inorganic compound particles is provided by coating and drying an aqueous solution containing the inorganic compound particles.

**7. (previously presented):** The method for production of a support for a lithographic printing plate precursor as claimed in claim 6, wherein the aqueous solution contains colloidal alumina particles.

**8. (previously presented):** The method for production of a support for a lithographic printing plate precursor as claimed in claim 4, wherein the treating solution contains a metal fluoride.

**9. (canceled).**

**10. (previously presented):** A support for a lithographic printing plate precursor that comprises a grained aluminum support having an anodic oxide film formed thereon and a layer of inorganic compound particles provided on the anodic oxide film, wherein a ratio of pore diameter of the layer of inorganic compound to pore diameter of the anodic oxide film is not less than 1.5; a ratio of fluorine concentration of the layer of inorganic compound to fluorine concentration of the anodic oxide film is not less than 2; and a ratio of silicon concentration of

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the layer of inorganic compound to silicon concentration of the anodic oxide film is not less than  
2.